Electronic States and Defects in Non-Crystalline and Nano-Crystalline Alternative Transition Metal Delelectrics

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additional support: DTRA and SRC

outline

(i) high-k dielectrics - 'atomic physics'*

(ii) <u>local site symmetries</u> - <u>strong d-state correlation</u> Hund's rule - high-spin <u>d-state occupancy</u>

(iii) <u>relative energies</u> of valence and conduction states scale with <u>neutral transition metal atomic energies</u>

(vi) O-atom vacancy - traps - many electron theory

limiting factor - device performance and reliability including radiation hardness

introduction to many electron theory

ground and first excited states of the H-atom



small difference, but significant with respect to getting it right

many electron wave functions ground state 1s¹2p⁰ to excited state 1s⁰2p¹ term symbol: ^{2S+1}LJ L - total orbital angular momentum, S - total spin, and J - maximum value of L+S - other J values stepped down by 1 →ground state $1s^{1}2p^{0}$: L = 0, S = 1/2, and J = 1/2 ²S_{1/2} with J = +1/2, -1/2, or ²S_{1/2,-1/2} (doubly degenerate) → excited state $1s^{0}2p^{1}$: L = 1, S = 1/2, and J = 3/2 ²P_{3/2} with J values of +3/2 and +1/2with spin-orbit splitting

atomic state symmetries 4- to 8-fold coordination spherically harmonics - SO3 symmetry- filled core levels lower symmetries for valence shell electrons

SO3	J	to	Oh	Td
S	0	→	A1g	A 1
р	1	→	T1u	T2
d	2	→	Eg + T2g	E + T2
f	3	→	A1u + T1u + T2u	A2 + T1 + T2
g	4	→	A1g + Eg + T2g + T1u	A1 + Eg + T2 + T1

basis set for <u>Si, Ge, III-V's, Si(GeO₂), Si(Ge)₃N₄</u>, Hf high-k's A_{1g} and B_{1g} - non-degenerate d-states - dz² and dx²-y²

A_{2g} - non-degenerate d-states – dxz (or dyz, dxy)

- **E** doubly degenerate d-states dz², dx²-y²
- T1 triply degenerate p-states px, py, pz

T2 - triply degenerate d-states - dxy, dxz, dyz

L_{2,3} spectra 2p⁶2d⁰ to 2p⁵3d¹ + (2p⁶4s⁰ to 2p⁵4d¹)satellite octahedral Ti⁴⁺

charge transfer multiplets theory applied to SrTiO3*



*F.M.F. de Groot et al, Phys. 42, 928 (1990);Phys. Rev. 42, 5459 (1990). *F. de Groot, A. Kotani, *Core level spectroscopy of solids* (Boca Raton, CRC Press, 2008). L_{2,3} spectra $2p^6sd^0$ to $2p^53d^1$

irreducible representation (IR)/ground state; A_{1g} A_{1g} is a one-dimensional symmetric "d-like" state final states must have "p-like" T_{1u} symmetries < A_{1g} | T_{1u} > = 0, equivalent to $\Delta L = \pm 1$

	SO3	J	to	Oh	triply degenerate final
ground state	S	0	→	A1g	different <i>mi</i> and <i>j</i>
	р	1	→	T1u	3 states
	d	2	≯	Eg + T2g	+
	f	3	→	A1u + T1u + T2u	3 states
	g	4	→	A1g + Eg + T2g + T1u	= 6 spectral features

L2,3 SrTiO3

TI⁴⁺ – ideal octahedral symmetry, Oh large energy difference between Ti atomic 3d and 4s states (-11 eV and - 6 eV, respectively) expect and observe 6 features



satellite features 2p⁶4s⁰ to 2p⁵4s¹

X-ray photon energies > L_{2,3} correlates with difference of 5 eV between 3d and 4s Ti atomic states

primitive unit cell distortion in TiO₂ grown on Ge template elongation of unit cell in z-direction removes 2 fold degeneracy of eg feature in L₂



ideal octahedron -- Oh symmetry

tetragonal distortion elongated in z-direction

differences in L_{2,3} between rutile and anatase unit cells "transported" to O K edge, and then into visible, vacuum ultra-violet (VUV) spectra as well



 (i) corrects previous interpretations of de Groot et al.
 conduction band is not joint DOS from Ti and Partial DOS!!*

(ii) connection between L_{2,3} and OK implications for band edge defects

* deGroot wrong!!

introduction to O-vacancy issues

many body theory gives proper interpretation of experiments, other theories do not

Robertson, Shlugger, etc... O-vacancy theory HfO₂, ZrO₂



many electron theory

ground state

three serious problems

 double or low-spin occupancy of Hf(Zr) d-states R,S ignored Hund's rules, and H Bethe 1929!! encouraged incorrect interpretation of SE, UCB and ISMT groups
 ignored NCSU group valence band spectra



medium range order (SRO) in SiO₂

MRO associated with d-states - non-degenerate A's, B's, doubly degenerate E's, and triply degenerate p-like T1's and d-like T2's

this is what makes SiO₂, and potentially GeO₂, and their oxynitrides unique with respect to band edge defect states

prelude to rest of story

major accomplishment is this fundamental intrinsic connection between many electron theory, synchrotron X-ray spectroscopy and defects

dielectrics with band edge A1g "s-like" states OK, only positive charge after radiation dosing – SiO2

HfO₂, etc. with eg or t_{2g} - O-vacancy/negative ion electron traps – negative charge after radiation dosing



SN(Q)* and Bell and Dean saw it "brushed it off!!"** Si-O 3rd and O-O 4th neighbor distances not predicted by CRNs





*J Du & LR Corrales, Phys Rev B 72, 092201 (2005). **RJ Bell and P Dean, Philos. Mag. 25 (No. 6) 1381-1398 (1972).

relative energy vs Si-O-Si bond angle Si-Si distance fixed - 0.31 nm - O'Keefe and Hyde (1978)



i) N-L*- J. Neufeind and K.-D. Liss, Bur Bunsen Phys Chem 100, 1341 (1996).
 ii) M-W** - R.L. Mozzi and B.E. Warren, J. Appl. Cryst. 2, 164 (1969).

O K edge excitations - coherent process for SiO2 OK edge
 (i) x-ray excitation to to virtual bound state and
 (ii) 1s core hole filling form O 2p π/σ valence band states



for Si L_{2,3} crystal field splitting of 1.8 eV is greater than S-O of 0.7 eV, whereas for ZrO₂ - spin-orbit, and pseudo spin orbit (13 eV and 10 eV) are greater than crystal field, ~3.5 eV



relative energies of features in 2nd derivative of Si L_{2,3} when "transported" to visible/VUV energy scale, correspond to features in SE, and absorption and reflection



2.5 eV is direct gap 1.1 eV is indirect gap phonon-assisted for symmetry

stronger transitions – d-states!! in reflection spectroscopic ellipsometry Yasuda and Aspnes JOSB, 1994

relevance to electrical performance and reliability, including rad-hardness of SiO₂



"s-states" SiO₂/GeO₂ more stress resistant than Hf-or Lu, La based high-k dielectrics – in which band edge states have d-character

relative energies of "s-state" band edge and higher energy "d-state" features are approximately the same in SiO₂ and GeO₂



O-atom vacancy defects are in middle of gap!! this makes SiO₂/GeO₂ special no band edge traps, or negative trapping after X-ray, γ-ray stress application to experimental results i) defect suppression in thin HfO2 - compare 2 nm and 4 nm thick films relationship to trap-assisted tunneling ii) defects in HfSiON ternaries compare with C-V characteristics

reminder: soft X-ray photoelectron spectroscopy valence band spectrum for nano-grain HfO2



Fig. 5. SXPS valence band spectrum for nano-crystalline HfO₂: 5d-state and defect features are identified.

O-vacancy electron states – 2 electrons/removed neutral O-atom Iowest energy states is high spin d² that can be on any one of four Hf atoms that border vacancy

excited states (d to d') are near conduction band are electron traps



ground triplet 's' state ³A2g to 3 triplet excited 'p'-states, ³T2g, ³T1g and ³T1g

NaCl structured NiO



Tanabe-Sugano diagrams also apply to d-d' transitions for O-atom vacancy defects, and negative ion states A Fujimori, et al., PR B30, 967 (1984).

same Tanabe-Sugano diagram and energy scale applies to d² O-atom vacancies in Y, Or, Hf oxides, and NiO in NaCI crystals



multiplicity and symmetry of features is determined by symmetry of the primitive unit cell



tetragonal nano-grains relatively high symmetry 3 sets of triplets

monoclinic nano-grains reduced symmetry more features mixing of triplet and singlet states

differences in O-vacancy band edge defects, and "d-state" features in OK edge spectra that correlate with film thickness



discrete character of defects and "d-state" features depends on unit cell size

physical thickness of nano-grain films constrains extended unit cell to be less than film thickness 2 nn thick films to less than critical size of ~ 3.0-3.5 nm necessary for cooperative Jahn-Teller distortions

differences in J-V correlate with differences in conduction band edge and band edge defect states (O-vacancies)







 (a) Thermal evolution of the O K₁ spectra for both HfO2 and HfSiON over a narrow energy region
 below doubly-degenerate Hf 5d conduction band edge states as a function of PDA temperature.

two deconvoluted peaks, labeled D(cb)1 and D(cb)2, indicate the defect states determined by Gaussian fits of the XAS O K1 edge spectra.

Iower density of defects by spectroscopy for HfSiON than HfO₂ - confirmed by CV



Capacitance-voltage (CV) for *n*-MOSCAPS 5nm HfSiON on *n*-type Ge (100

Iowest trap density same as Saraswat's (Stanford Univ) best

HfSiON on Si - X-ray stress similar to SiO2 no negative fixed charge as in HfO2

defects lower than in HfO2 agrees with XAS

(HfO2)0.3(SiO2)0.3(Si3N4)0.4 chemically-controlled composition stable to > 1000°C defect generation - X-ray stress "SiO2 look alike with a higher dielectric constant ~10-11, and a 5000 fold decrease in leakage current !!



*AFOSR, Vanderbilt MURI Jim Felix, Dan Fleetwood,....

this review presentation is dedicated to

i) Isaac Besuker and Victor Pollinger -- my mentors and friends within the Jahn-Teller theoretical chemistry community,

and

 ii) Rick Garfunkel for his <u>much appreciated critique</u> of a "bad" SRC review presentation a few weeks ago this improved talk is my response to his critique

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